Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	116	(((enlarge\$3 resiz\$3 (re adj siz\$3) increas\$3 expand\$3 broaden\$3 add\$3 augment\$5 expansion maximize maximum amplify magnif\$8) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 09:22
L4	6	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 augment\$5 expansion amplif\$3 magnif\$8) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 09:38
L5	0	"6710847".pn. and (trim)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 09:39

L6	2	(((enlarg\$3 resiz\$3 siz\$3 (re adj siz\$3) increas\$3 augment\$5 expansion amplif\$3 magnif\$8) with pattern with (lin\$3 margin correct\$3 thin fine width\$3 spac\$3 densit\$3 feature cd (critical near dimension)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc)) and (((trim\$4 (multi adj phase near transistion)) near2 mask) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 09:50
L7	2	(((enlarg\$3 resiz\$3 siz\$3 (re adj siz\$3) increas\$3 augment\$5 expansion amplif\$3 magnif\$8) with (lin\$3 margin correct\$3 thin fine width\$3 spac\$3 densit\$3 feature cd (critical near dimension)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask) same (opc (optical with (correct\$3 effect\$3))) same ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (window opaque\$3)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:10
L8	113	opc with enlarg\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:11

L9	31	opc with enlarg\$3 and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;	OR	ON	2006/08/05 10:30
L10	1	"6710847".pn. and (proximit\$3 with (correct\$3 effect))	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:31
L11	1	"6710847".pn. and (optical with (correct\$3 effect))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:47
L12	191	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 augment\$5 expansion maximize maximum amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:49

L13	179	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 augment\$5 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	
L14	179	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:50

L15	160	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near2 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical near2 (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:50
L16	117	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near2 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical near2 (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:51

L17	99	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) near5 (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near2 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical near2 (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:51
L18		(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) near5 (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near2 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical near2 (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) near5 (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:52

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L19	21	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 amplify\$8 magnif\$8) near5 (lin\$3 margin cd (critical near (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near2 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical near2 (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) near5 (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:55
L20	177	(((enlarg\$3 increas\$3 augment\$5 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:55

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L21	148	(((enlarg\$3 increas\$3 augment\$5 amplify\$8 magnif\$8) near5 (lin\$3 margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:55
L22	122	(((enlarg\$3 increas\$3 augment\$5 amplify\$8 magnif\$8) near5 (lin\$3 pattern margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement feature)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:56

L23	118	(((enlarg\$3 increas\$3 augment\$5 amplify\$8 magnif\$8) near5 (lin\$3 pattern margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:56
L24	111	(((enlarg\$3 increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 10:59

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L25	23864041	(((enlarg\$3 increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3)))) @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 11:00
L26	90	(((enlarg\$3 increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 11:01

<u> </u>		/ //	LIC DCDLID-	OB	ON	2006/08/05 11:06
L27	25	(((enlarg\$3 increas\$3 amplif\$8	US-PGPUB; USPAT;	OR	ON	2000/00/05 11.00
		magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension	USOCR;			
		measurement features)) thin fine	EPO; JPO;			
		width\$3 spac\$3 feature)) same (rule	DERWENT;			
		guideline constraints parameter	IBM_TDB			
		predetermined (guide adj line)			1	
	ļ	specification requirements				
		conditions)) and ((proximity near5				
		(effect\$3 correct\$4)) or ope or ppc)				
		and ((opc (optical with (correct\$3				
	ļ	effect\$3)))) and ((first primary				
		initial) near2 (photomask (photo adj				[
		(mask reticle)) mask reticle)) and (
		((second trim\$4 (multi adj phase near transistion)) near2 mask)) and				
		((reduc\$5 decreas\$3 shrink\$3		1		
		diminish\$3 lessen\$3 truncat\$5	į			
		cutback) with (width pitch densit\$3				
		spac\$3)) and (((proximity near5				
		(effect\$3 correct\$4)) or ope or ppc)				
		same (photomask (photo adj (mask			İ	
		reticle)) mask reticle)) and (
		(photomask (photo adj (mask				
		reticle)) mask reticle) same ((opc				
		(optical with (correct\$3 effect\$3))))				
	1) and @ad<"20030326"				

L28	3	(((enlarg\$3 increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature)) same (rule guideline constraints parameter predetermined (guide adj line) specification requirements conditions)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((complementary trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3))))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 11:10

1.22		/ //	LIC DCDUS	OD	ON	2006/00/05 11:10
L29	25	(((enlarg\$3 resiz\$3 (siz\$3 near2	US-PGPUB;	OR	ON	2006/08/05 11:18
		(fix\$3 correct\$3)) increas\$3	USPAT;			
		amplif\$8 magnif\$8) near5 (lin\$3	USOCR;			
		pattern margin "cd" (critical near	EPO; JPO;			İ
		(dimension measurement features))	DERWENT;			
		thin fine width\$3 spac\$3 feature))	IBM_TDB			
		same (rule guideline constraints		1		
		parameter predetermined (guide adj				
		line) specification requirements				
		conditions)) and ((proximity near5				
		(effect\$3 correct\$4)) or ope or ppc)				
		and ((opc (optical with (correct\$3				
		effect\$3)))) and ((first primary				
		initial) near2 (photomask (photo adj				
		(mask reticle)) mask reticle)) and (
		((second complementary trim\$4				
		(multi adj phase near transistion))				
		near2 mask)) and ((reduc\$5		İ		
		decreas\$3 shrink\$3 diminish\$3				
		lessen\$3 truncat\$5 cutback) with				
		(width pitch densit\$3 spac\$3)) and				
		(((proximity near5 (effect\$3				
		correct\$4)) or ope or ppc) same				
	Ì	(photomask (photo adj (mask				
		reticle)) mask reticle)) and (
		(photomask (photo adj (mask				
		reticle)) mask reticle) same ((opc				
		(optical with (correct\$3 effect\$3))))				
) and @ad<"20030326"				

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130	-	(/(aplarat2 rocizt2 /cizt2 poar2	US-PGPUB;	OR	ON	2006/08/05 11:19
L30	3	(((enlarg\$3 resiz\$3 (siz\$3 near2 (fix\$3 correct\$3)) increas\$3	USPAT;		ON	2000/00/03 11.19
		amplif\$8 magnif\$8) near5 (lin\$3	USOCR;			
		pattern margin "cd" (critical near	EPO; JPO;			
		(dimension measurement features))	DERWENT;			
		thin fine width\$3 spac\$3 feature))	IBM_TDB			
		same (rule guideline constraints	_			
		parameter predetermined (guide adj				
		line) specification requirements				
		conditions)) and ((proximity near5				
		(effect\$3 correct\$4)) or ope or ppc)				
		and ((opc (optical with (correct\$3				
		effect\$3)))) and ((first primary				
		initial) near2 (photomask (photo adj				
		(mask reticle)) mask reticle)) and (((complementary trim\$4 (multi adj				
		phase near transistion)) near2				•
		mask)) and ((reduc\$5 decreas\$3			1	
İ		shrink\$3 diminish\$3 lessen\$3				
		truncat\$5 cutback) with (width pitch				
}		densit\$3 spac\$3)) and ((]	
		(proximity near5 (effect\$3				
		correct\$4)) or ope or ppc) same				
		(photomask (photo adj (mask				
		reticle)) mask reticle)) and (
		(photomask (photo adj (mask				
		reticle)) mask reticle) same ((opc				
		(optical with (correct\$3 effect\$3))))				
) and @ad<"20030326"			<u> </u>	

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L31	5	(((enlarg\$3 resiz\$3 (siz\$3 near2 (fix\$3 correct\$3)) increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature)) same (rule guideline constraints parameter predetermined (guide adj line) specification requirements conditions)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((photomask (photo adj (mask reticle)) mask reticle)) and (((complementary trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and (((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 11:33
L32	36	(((enlarg\$3 resiz\$3 (siz\$3 near2 (fix\$3 correct\$3)) increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern layout margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((complementary trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3)))) and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 13:37

L33	2	"20040248045"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 14:27
L34	2	"20040248045" and (minimum with (spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 14:27
L35	1	"20030106037" and (minimum with (spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 14:35
L36	0	"20030106037" and (reduc\$4 with (spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 14:36
L37	0	"20030106037" and (decrease with (spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:37
L38	1	"20020160281" and (decrease with (spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:37
L39	0	"20020160281" and trim	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:38
L40	1	"20020160281" and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:46

L41	0	"20030106037" and (estimat\$3 calculat\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:46
L42	0	"20030106037" and (determin)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:46
L43	0	"20030106037" and (determin\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:46
L44	0	"20030106037" and complementary	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:46
L45	1	"20030106037" and align\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:52
L46	1	"20030106037" and (minimum with width)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/05 16:52
S1	528	(prepar\$3 produc\$3 construc\$4 develop\$5 provid\$4 forming formation form generat\$3 build\$3 contriv\$3 fabricat\$5 creat\$3) with mask with data with transfer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 11:55
S2	2	S1 and 716/?.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 11:59

S3	1	"20040248045" and transfer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 12:04
S4	30	(prepar\$3 produc\$3 construc\$4 develop\$5 provid\$4 generat\$3 build\$3 contriv\$3 fabricat\$5 creat\$3) with mask with data with transfer and 430/?.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 12:06
S5	23	S4 and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 14:56
S6	1	S5 and window	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:00
S7	2	"20040248045" and (window)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 14:56
S8	40	window with expos\$5 and 716/?. ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:00
S9	121	window with expos\$5 and 716/19. ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:03
S10	140	window near4 (mask reticle) and "716"/\$2.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:38

S11	221	lithography near margin	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:36
S12	36	window near4 (mask reticle) with (expos\$6) and "716"/\$2.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:42
S13	24	window near4 (pattern) with (expos\$6) and "716"/\$2.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 15:48
S14	2	(prepar\$3 produc\$3 construc\$4 develop\$5 provid\$4 form formation forming formed generat\$3 build\$3 contriv\$3 fabricat\$5 creat\$3) near5 (((mask pattern exposure reticle) near data)) and (((mask pattern exposure reticle) near data) with (resiz\$3 enlarg\$3 (re adj siz\$3))) and (opc (optical with proximity with correction)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) near5 width with pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 16:03
S15	2	(((mask pattern exposure reticle) near data)) and (((mask pattern exposure reticle) near data) with (resiz\$3 enlarg\$3 (re adj siz\$3))) and (opc (optical with proximity with correction)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) near5 width with pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 16:04
S16	17	(((mask pattern exposure reticle) near data)) and (((pattern exposure)) with (resiz\$\$\footnote{3}\$ enlarg\$\$3 (re adj siz\$\$3))) and (opc (optical with proximity with correction)) and ((reduc\$\$5 decreas\$\$3 shrink\$\$3 diminish\$\$3 lessen\$\$3 truncat\$\$5 cutback) near\$\$5 width with pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 16:35

S17	63	resiz\$3 with ((mask pattern exposure reticle) near data)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:00
S18	411	mask near data near process\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:00
S19	292	mask near data near process\$4 and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:03
S20	2	(mask adj data) and "20040248045"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:16
S21	2	align\$5 and "20040248045"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:32
S22	144	(((((mask pattern exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3)) and (pattern with (transfer\$5 expos\$5)) and (first with (mask reticle) with (width densit\$3 pitch spac\$3)) and (second with (mask reticle) with (correspond\$5 align\$5 equivalen\$3 complementary matching) with (first with (mask reticle))) and (pattern with (rules specification constraint margin guideline (guide adj line)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:37
S23	119	S22 and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:38

S24	103	S22 and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;	OR	ON	2006/08/04 17:38
S25	21	S24 and (opc or (proximity near correct\$3))	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:39
S26	81	(((((mask pattern exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3)) and (pattern with (transfer\$5 expos\$5)) and (first with (mask reticle) with (width densit\$3 pitch spac\$3)) and (second with (mask reticle) with (correspond\$5 align\$5 equivalen\$3 complementary matching) with (first with (mask reticle))) and (pattern with (rules specification constraint margin guideline (guide adj line))) and (reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:40
S27	66	S26 and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:41
S28	59	S26 and @ad<"20030326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:42
S29	10	S28 and (opc or (proximity near correct\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:42

S30	21	((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3)) and (pattern with (transfer\$5 expos\$5)) and (first with (\$5mask (photo adj (mask reticle)) reticle) with (width densit\$3 pitch spac\$3)) and (second with (\$5mask (photo adj (mask reticle)) reticle) with (correspond\$5 align\$5 equivalen\$3 complementary matching) with (first with (\$5mask (photo adj (mask reticle)) reticle)) and (pattern with (rules specification constraint margin guideline (guide adj line))) and (reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3) and (opc or (proximit\$3 near correct\$3) ret (enhancement with technique) (resolution with enhancement))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 17:48
S31	15	S30 and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:22
532	9658	(mask reticle) near set	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:23
S33	1	"20040248045" and enlarging	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:26
S34	1	"20040248045" and (enlarg\$3 increas\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:28

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S35	50736	((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) same (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3) with (width spac\$3 pitch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:29
S36	23506	((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3) with (width spac\$3 pitch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:29
S37	2083	((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 increas\$3 magnif\$8 larg\$3) with (width spac\$3 pitch\$3)) and @ad<"20030326" and ("716"/\$2.ccls. "430"/\$4.ccls."	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:33
S38	22844	(resiz\$3 enlarg\$3 increas\$3 larg\$3) with (width spac\$3 pitch\$3) with pattern	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:37
S39	434	(resiz\$3 enlarg\$3 increas\$3 larg\$3) with (width spac\$3 pitch\$3) with pattern same (\$5mask (photo adj (mask reticle)) reticle) with (first initial primary) same (trim second\$3) with (\$5mask (photo adj (mask reticle)) reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:38
S40	239	(resiz\$3 enlarg\$3 increas\$3 larg\$3) with (width spac\$3 pitch\$3) with pattern same (\$5mask (photo adj (mask reticle)) reticle) near5 (first initial primary) same (trim second\$3) near5 (\$5mask (photo adj (mask reticle)) reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:39
S41	13	S40 and "716"/\$2.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:40

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S42	3053	pattern with distribut\$3 with (mask reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 18:40
S43	85	pattern near distribut\$3 near (mask reticle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 19:05
S46	62	pattern same (resiz\$3 with (value quantity number))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 19:49
S47	289	(enlarge\$3 resiz\$3 (re adj siz\$3) increas\$3 expand\$3 broaden\$3 add\$3 augment\$5 expansion maximize maximum amplify) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((opc ope ret ppc (proximity near2 (correction effect)) (resolution near2 enhancement))) and ((lin\$3 with (spac\$3 densit\$3 width)) same pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 19:54
S48	98	(((enlarge\$3 resiz\$3 (re adj siz\$3) increas\$3 expand\$3 broaden\$3 add\$3 augment\$5 expansion maximize maximum amplify) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature)) same (rule guideline constraints predetermined (guide adj line) specification requirements conditions)) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((opc ope ret ppc (proximity near2 (correction effect)) (resolution near2 enhancement))) and ((lin\$3 with (spac\$3 densit\$3 width)) same pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/04 19:55

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